



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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|-----------|---|-----------------------|---|---------------------|
| Applicant | : | Fukuda et al. |) | Group Art Unit 1763 |
| | | |) | |
| Appl. No. | : | 09/511,934 |) | |
| | | |) | |
| Filed | : | February 24, 2000 |) | |
| | | |) | |
| For | : | THIN-FILM FORMING |) | |
| | | APPARATUS HAVING AN |) | |
| | | AUTOMATIC CLEANING |) | |
| | | FUNCTION FOR CLEANING |) | |
| | | THE INSIDE |) | |
| | | |) | |
| Examiner | : | R. Kackar |) | |

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AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

In response to the Office Action mailed November 20, 2002 (Paper number 13), please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel Claim 8.

Please amend Claim 1 as follows:

1. (Fifth amended) A thin film forming apparatus comprising:
a reaction chamber for forming a film formation temperature of 500°C or higher a thin film on a workpiece placed on a susceptor and below a showerhead provided in the reaction chamber, said susceptor being made of aluminum nitride and provided with a heater for heating the workpiece, said reaction chamber being provided with a conveyer for loading and unloading the workpiece into and from the reaction chamber; and
a cleaning device for cleaning unwanted deposits adhering to the inside of the reaction chamber at predetermined intervals, said cleaning device comprising: